L Number	Hits	Search Text	DB	Time stamp
16	132	ZAMPINI-A ZAMPINI-ANTHONY	USPAT;	2004/07/07 11:08
			US-PGPUB;	
			EPO; JPO;	·
			DERWENT	
17	72894	acetal ketal	USPAT;	2004/07/07 11:09
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
18	18	(ZAMPINI-A ZAMPINI-ANTHONY) and (acetal ketal)	USPAT;	2004/07/07 11:09
			US-PGPUB;	
			EPO; JPO;	
10		//7.4.4.PI.M. 4. 7.4.4.PI.M. 4.1.7.4.4.P.M. 4.1.4.4.1.4.4.4.4.4.4.4.4.4.4.4.4.4.4.	DERWENT	
19	8	((ZAMPINI-A ZAMPINI-ANTHONY) and (acetal ketal)) and ((acid	USPAT;	2004/07/07 12:36
		photoacid) adj labile)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
20	1322	(acetal ketal) and ((acid photoacid) adj labile)	USPAT;	2004/07/07 11:13
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
21	428	((acetal ketal) and ((acid photoacid) adj labile)) and (430/\$.ccls.)	USPAT;	2004/07/07 11:14
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
22	281	(fluorinated fluorine fluoro) and (((acetal ketal) and ((acid photoacid)	USPAT;	2004/07/07 11:26
		adj labile)) and (430/\$.ccls.))	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
23	3620	disulfide same oxygen	USPAT;	2004/07/07 11:27
			US-PGPUB;	
	ĺ		EPO; JPO;	
			DERWENT	
24	312	(disulfide same oxygen) and (resist photoresist)	USPAT;	2004/07/07 11:46
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
25	14	((disulfide same oxygen) and (resist photoresist)) and ((acid photoacid)	USPAT;	2004/07/07 11:45
		adj labile)	US-PGPUB;	
			EPO; JPO;	
26	1.00		DERWENT	
26	160	(disulfide adj compound) same (oxygen)	USPAT;	2004/07/07 11:56
			US-PGPUB;	
			EPO; JPO;	!
27		// P 16 1 P	DERWENT	
27	0	((disulfide adj compound) same (oxygen)) and ((acid photoacid) adj	USPAT;	2004/07/07 11:45
		labile)	US-PGPUB;	
			EPO; JPO;	
28	F.3		DERWENT	
20	53	((disulfide adj compound) same (oxygen)) and (resist photoresist)	USPAT;	2004/07/07 12:37
			US-PGPUB;	·
			EPO; JPO;	
29	11	(disulfide edi commound) and () to be a second as a second	DERWENT	
23	11	(disulfide adj compound) and (resist photoresist) and ((acid photoacid)	USPAT;	2004/07/07 12:36
		adj labile)	US-PGPUB;	
			EPO; JPO;	
20	313	2	DERWENT	
30	312	2-mercaptothiazole	USPAT;	2004/07/07 12:36
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	İ

9 2-mercaptothiazole and ((acid photoacid) adj labile) USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/25/25 - 2 :
EPO; JPO;	2004/07/07 12:36
DEPMENT	
32 14 2-mercaptothiazole and (resist photoresist) USPAT;	2004/07/07 12:37
US-PGPUB;	
EPO; JPO;	
DERWENT	
33 14 (2-mercaptothiazole and (resist photoresist)) not (2-mercaptothiazole USPAT;	2004/07/07 12:40
and ((acid photoacid) adj labile)) US-PGPUB;	
EPO; JPO;	
DERWENT 34 6014 (photoacid acid) adi labile	0001/00/00
(357,117)	2004/07/07 12:41
US-PGPUB;	
EPO; JPO;	
DERWENT 35 1167 alicylic admantyl USPAT;	2004/07/07 12:41
US-PGPUB;	2004/07/07 12:41
EPO; JPO;	
DERWENT	
36 36775 alicylic adamantyl norbornyl norbornene adamantane USPAT;	2004/07/07 12:41
US-PGPUB;	200-1107707 12.41
EPO; JPO;	
DERWENT	
37 5 2-mercaptothiazole and ((photoacid acid) adj labile) and (alicylic USPAT;	2004/07/07 12:42
adamantyl norbornyl norbornene adamantane) US-PGPUB;	
EPO; JPO;	
DERWENT	
38 6029 (organic adj solvent) and (basic adj compound) USPAT;	2004/07/07 12:42
US-PGPUB;	
EPO; JPO;	
DERWENT	
39 293861 surfactant USPAT;	2004/07/07 12:42
US-PGPUB;	
EPO; JPO;	
DERWENT 40 1311 dissolution adj inhibitor USPAT:	2004/07/07 12 42
40	2004/07/07 12:43
EPO; JPO;	
DERWENT	
41 1876 (thiol disulfide thiolsulfonate) adj derivative USPAT;	2004/07/07 12:43
US-PGPUB;	200 1/0//0/ 12.43
EPO; JPO;	
DERWENT	
42 450751 resist photoresist USPAT;	2004/07/07 12:43
US-PGPUB;	
EPO; JPO;	
DERWENT	
43 1797737 resin USPAT;	2004/07/07 12:43
US-PGPUB;	
EPO; JPO;	
DERWENT 9 (resin (resist photoresist)) and ((thiol disulfide thiolsulfonate) adi USPAT:	
Con (asset protestes) and ((anot disamore unoisanottate) adj	2004/07/07 12:48
EPO; JPO; DERWENT	
	2004/07/07 12:51
	2004/07/07 12:51
45 37 ((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) USPAT;	
45 37 ((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) USPAT; (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist US-PGPUB;	
45 37 ((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) USPAT; (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 EPO; JPO;	
45 37 ((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 EPO; JPO; 430/913 430/917 430/921 430/942).ccls.) 46 37 ((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) USPAT; US-PGPUB; PO; JPO; DERWENT	2004/07/07 13:07
45 37 ((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 EPO; JPO; 430/913 430/917 430/921 430/942).ccls.) 46 47 (((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist USPAT;	2004/07/07 13:07
45 37 ((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327 EPO; JPO; 430/913 430/917 430/921 430/942).ccls.) 46 37 ((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) USPAT; US-PGPUB; PO; JPO; DERWENT	2004/07/07 13:07

47	4	saWATANABE-SATOSHI WATANABE-SATOSHI-CANON-KABUSHI	USPAT;	2004/07/07 12:57
		WATANABE-SATOSHI-C-O-NIPPON-ST	US-PGPUB;	
		WATANABE-SATOSHI-C-O-SPECIALTY	EPO; JPO;	
		WATANABE-SATOSHI-SHIN-ETSU-CHE	DERWENT	
48	1177	WATANABE-SATOSHI WATANABE-SATOSHI-CANON-KABUSHI	USPAT;	2004/07/07 13:05
		WATANABE-SATOSHI-C-O-NIPPON-ST	US-PGPUB;	200 1107707 13:03
		WATANABE-SATOSHI-C-O-SPECIALTY	EPO; JPO;	
		WATANABE-SATOSHI-SHIN-ETSU-CHE	DERWENT	
49	2		USPAT;	2004/07/07 13:05
,,,	_	WATANABE-SATOSHI-C-O-NIPPON-ST	US-PGPUB;	2004/07/07 13:03
		WATANABE-SATOSHI-C-O-SPECIALTY		
		WATANABE-SATOSHI-SHIN-ETSU-CHE) and ((thiol disulfide	EPO; JPO;	
			DERWENT	
50		thiolsulfonate) adj derivative)		0.001/0.000
	0		USPAT	2004/07/07 13:05
51	145158	(\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)	USPAT;	2004/07/07 13:09
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
52	8	(1) The state of t	USPAT;	2004/07/07 13:13
		(WATANABE-SATOSHI WATANABE-SATOSHI-CANON-KABUSHI	US-PGPUB;	
		WATANABE-SATOSHI-C-O-NIPPON-ST	EPO; JPO;	
		WATANABE-SATOSHI-C-O-SPECIALTY	DERWENT	
		WATANABE-SATOSHI-SHIN-ETSU-CHE)		
53	6	(((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)) and	USPAT;	2004/07/07 13:21
		(WATANABE-SATOSHI WATANABE-SATOSHI-CANON-KABUSHI	US-PGPUB;	200 1/0//0/ 13:21
		WATANABE-SATOSHI-C-O-NIPPON-ST	EPO; JPO;	
		WATANABE-SATOSHI-C-O-SPECIALTY	DERWENT	
		WATANABE-SATOSHI-SHIN-ETSU-CHE)) not	DERVERT	
		((WATANABE-SATOSHI WATANABE-SATOSHI-CANON-KABUSHI		
		WATANABE-SATOSHI-C-O-NIPPON-ST		
	ľ	WATANABE-SATOSHI-C-O-SPECIALTY		
		WATANABE-SATOSHI-C-O-SPECIAETT WATANABE-SATOSHI-SHIN-ETSU-CHE) and ((thiol disulfide		
		thiolsulfonate) adj derivative))		
	182614		1100.7	0000100100
-	102014	thiol disulfide thiolsulfonate mercapto\$	USPAT;	2004/07/06 19:03
			US-PGPUB;	
			EPO; JPO;	
	2424		DERWENT	
-	2424	ped (post-exposure adj delay) (post adj exposure adj delay)	USPAT;	2003/09/03 11:18
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	409168	resist photoresist	USPAT;	2003/08/28 17:00
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	17620	((acid photoacid) near generat\$4) (photoactive near compound)	USPAT;	2003/09/03 16:59
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
_	22477	(basic adj compound) (nitrogen-containing adj compound)	USPAT;	2003/09/03 16:59
		, , , , , , , , , , , , , , , , , , , ,	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	266188	surfactant	USPAT;	2003/09/03 16:59
	-30.00		US-PGPUB;	2003/03/03 10:39
			EPO; JPO;	
_	1095	dissolution adi inhibitor	DERWENT	2022/20/22 := 52
_	1095	dissolution adj inhibitor	USPAT;	2003/09/03 17:00
			US-PGPUB;	
			EPO; JPO;	
	L		DERWENT	

-	98	(thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure adj delay) (post adj exposure adj delay)) and (resist photoresist) and (((acid photoacid) near generat\$4) (photoactive near compound))	USPAT; US-PGPUB; EPO; JPO;	2003/08/28 17:01
	0.0		DERWENT	
-	98	((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure adj	USPAT;	2003/08/28 17:01
		delay) (post adj exposure adj delay)) and (resist photoresist) and	US-PGPUB;	
		(((acid photoacid) near generat\$4) (photoactive near compound))) and	EPO; JPO;	
_	92	((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure adj	DERWENT USPAT;	2003/08/28 17:01
	"-	delay) (post adj exposure adj delay)) and (resist photoresist) and	US-PGPUB;	2003/00/20 17:01
		(((acid photoacid) near generat\$4) (photoactive near compound))) and	EPO; JPO;	
		surfactant	DERWENT	
-	98	((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure adj	USPAT;	2004/06/29 13:23
		delay) (post adj exposure adj delay)) and (resist photoresist) and	US-PGPUB;	
		(((acid photoacid) near generat\$4) (photoactive near compound))) and	EPO; JPO;	
		(surfactant (dissolution adj inhibitor) ((basic adj compound)	DERWENT	
	-	(nitrogen-containing adj compound)))		
-	1	(((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure	USPAT;	2003/08/28 17:02
		adj delay) (post adj exposure adj delay)) and (resist photoresist) and (((acid photoacid) near generat\$4) (photoactive near compound))) and	US-PGPUB;	
		(surfactant (dissolution adj inhibitor) ((basic adj compound)	EPO; JPO; DERWENT	
		(nitrogen-containing adj compound)))) and ((thiol disulfide	DERWEINT	
		thiolsulfonate mercapto\$) same (ped (post-exposure adj delay) (post		
		adj exposure adj delay)))		
-	4	(thiol disulfide thiolsulfonate mercapto\$) same (ped (post-exposure	USPAT;	2003/08/28 17:06
		adj delay) (post adj exposure adj delay))	US-PGPUB;	
			EPO; JPO;	
	97	(((third disulfide thirds)) for the many (100) and (101)	DERWENT	
-	97	(((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure adj delay) (post adj exposure adj delay)) and (resist photoresist) and	USPAT;	2003/08/28 17:06
		(((acid photoacid) near generat\$4) (photoactive near compound))) and	US-PGPUB; EPO; JPO;	
	İ	(surfactant (dissolution adj inhibitor) ((basic adj compound)	DERWENT	
		(nitrogen-containing adj compound)))) not ((thiol disulfide		
		thiolsulfonate mercapto\$) same (ped (post-exposure adj delay) (post		
		adj exposure adj delay)))		
-	126812	\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10	USPAT;	2003/09/03 18:44
			US-PGPUB;	
			EPO; JPO;	
-	3	(\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) same (ped	DERWENT USPAT;	2003/08/28 18:38
	_	(post-exposure adj delay) (post adj exposure adj delay))	US-PGPUB;	2003/00/20 10:30
}		, ,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	EPO; JPO;	
			DERWENT	
-	6888	(\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist	USPAT;	2003/08/28 18:40
		photoresist)	US-PGPUB;	
			EPO; JPO;	
	71	((\$10)bio(\$10 \$10dio.)(\$1d-\$10 \$10dii 16	DERWENT	
	/	((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near	USPAT;	2003/09/03 11:30
		compound)) and ((lacid photoacid) near generat§4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj	US-PGPUB; EPO; JPO;	
		compound)) and surfactant	DERWENT	
-	30	(((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist	USPAT;	2004/07/07 12:51
		photoresist)) and (((acid photoacid) near generat\$4) (photoactive near	US-PGPUB;	_30 1/0//0/ 12.31
		compound)) and ((basic adj compound) (nitrogen-containing adj	EPO; JPO;	
		compound)) and surfactant) and (dissolution adj inhibitor)	DERWENT	

·				
-	25	((((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist	USPAT;	2004/06/29 13:38
		photoresist)) and (((acid photoacid) near generat\$4) (photoactive near	US-PGPUB;	
		compound)) and ((basic adj compound) (nitrogen-containing adj	EPO; JPO;	
		compound)) and surfactant) and (dissolution adj inhibitor)) not	DERWENT	
		((((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure		
		adj delay) (post adj exposure adj delay)) and (resist photoresist) and		
		(((acid photoacid) near generat\$4) (photoactive near compound))) and		
		(surfactant (dissolution adj inhibitor) ((basic adj compound)		
		(nitrogen-containing adj compound)))) not ((thiol disulfide		
		thiolsulfonate mercapto\$) same (ped (post-exposure adj delay) (post		
		adj exposure adj delay))))		
-	2	(ped (post-exposure adj delay) (post adj exposure adj delay)) near	USPAT;	2003/09/03 11:28
		stabilizer	US-PGPUB;	
		,	EPO; JPO;	
			DERWENT	
-	0	(ped (post-exposure adj delay) (post adj exposure adj delay)) near	USPAT;	2003/09/03 11:24
		(additive)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	2430	ped (post-exposure adj delay) (post adj exposure adj delay)	USPAT;	2003/09/03 11:19
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	2163	(thiol disulfide thiolsulfonate) near derivative	USPAT;	2003/09/03 18:43
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	0	((ped (post-exposure adj delay) (post adj exposure adj delay)) same	USPAT;	2003/09/03 18:16
	1	((thiol disulfide thiolsulfonate) near derivative)) not ((ped	US-PGPUB;	
		(post-exposure adj delay) (post adj exposure adj delay)) near	EPO; JPO;	
		stabilizer)	DERWENT	
-	1	(ped (post-exposure adj delay) (post adj exposure adj delay)) same	USPAT;	2003/09/03 11:19
		((thiol disulfide thiolsulfonate) near derivative)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	21	(ped (post-exposure adj delay) (post adj exposure adj delay)) and	USPAT;	2003/09/03 11:19
		((thiol disulfide thiolsulfonate) near derivative)	US-PGPUB;	
	1		EPO; JPO;	
		2002202006 LIBBNI	DERWENT	000015-15-5
1	705	2002303986.URPN.	USPAT	2003/09/03 11:23
-	/03	(thiol disulfide thiolsulfonate) near agent	USPAT;	2003/09/03 11:24
	•		US-PGPUB;	
			EPO; JPO;	
_	10	(ped (post-exposure adj delay) (post adj exposure adj delay)) near5	DERWENT	2002/00/02 ** * *
	10	(agent) (post-exposure auj deray) (post auj exposure auj deray)) near5	USPAT;	2003/09/03 11:24
		(agony	US-PGPUB;	
			EPO; JPO;	
_	236	(ped (post-exposure adj delay) (post adj exposure adj delay)) near6	DERWENT	2002/00/02 11 05
	250	stabil\$6	USPAT;	2003/09/03 11:29
		σιανήψο	US-PGPUB;	
			EPO; JPO;	
_	1	((ped (post-exposure adj delay) (post adj exposure adj delay)) near6	DERWENT	2002/00/02 ** 22
	'	stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)	USPAT;	2003/09/03 11:29
		stability of same (fullor distalling thiolsullonate) hear derivative)	US-PGPUB;	
			EPO; JPO;	
_	225	((ped (post-exposure adj delay) (post adj exposure adj delay)) near6	DERWENT	2002/00/02 16 50
	223	stabil\$6) and (resist photoresist)	USPAT;	2003/09/03 16:59
		stability of and (resist priotoresist)	US-PGPUB;	
			EPO; JPO; DERWENT	
_	126948	\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10		2002/00/02 11:20
	120540	4 complete a tomporting to a tominorational (s)	USPAT;	2003/09/03 11:39
			US-PGPUB; EPO; JPO;	
			DERWENT	
	Ll		DEVANCIAL	

-	11	(((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)	USPAT; US-PGPUB; EPO; JPO;	2003/09/03 11:52
-	2	("6099880").PN.	DERWENT USPAT;	2003/09/03 11:52
			US-PGPUB; EPO; JPO; DERWENT	
-	0 112931	20020136981.URPN. THIOL DISULFIDE THIOLSULFONATE	USPAT USPAT;	2003/09/03 12:07 2003/09/03 14:06
			US-PGPUB; EPO; JPO; DERWENT	
-	7137	(THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE	USPAT; US-PGPUB;	2003/09/03 14:06
	1564	((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE)	EPO; JPO; DERWENT USPAT;	2002/00/02 14 17
	1304	SAME STABIL\$6	US-PGPUB; EPO; JPO;	2003/09/03 14:17
-	121	(((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE)	DERWENT USPAT;	2003/09/03 14:17
		SAME STABIL\$6) AND (RESIST PHOTORESIST)	US-PGPUB; EPO; JPO; DERWENT	
-	15	(US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or	USPAT; US-PGPUB;	2003/09/03 14:26
		US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or	JPO	
-	120	US-20020147259-\$).did. or (JP-2002303986-\$).did. ((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT	USPAT; US-PGPUB;	2003/09/03 14:26
		((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or	EPO; JPO; DERWENT	
		US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$).did. or (JP-2002303986-\$).did.)		
-	120	(((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT	USPAT; US-PGPUB;	2003/09/03 17:01
	į	((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or	EPO; JPO; DERWENT	
		US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj		
		delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6		
		stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) ((((ped (post-exposure adj delay)) near6		
		stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)))		
-	17642	((acid photoacid) near generat\$4) (photoactive near compound)	USPAT; US-PGPUB; EPO; JPO;	2003/09/03 14:27
~	266458	surfactant	DERWENT USPAT; US-PGPUB;	2003/09/03 14:27
			EPO; JPO; DERWENT	

-	0	((((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE)	USPAT;	2003/09/03 14:27
İ		SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT	US-PGPUB;	
		((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$	EPO; JPO;	
		or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or	DERWENT	
		US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or		
		US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or		
		US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near		
		stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj		
		delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near5 (agent))		,
	1	(((ped (post-exposure adj delay) (post adj exposure adj delay)) near6		
ŀ		stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) ((((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near6		
	1	stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10		
		\$10thiolsulfonate\$10)))) AND (((acid photoacid) near generat\$4)		
		(photoactive near compound)) AND surfactant		
1_	0	(((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE)	USPAT:	2003/09/03 14:28
		SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT	US-PGPUB;	2003/09/03 14:26
		((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$	EPO; JPO;	
		or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or	DERWENT	
		US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or	DEKWENT	
		US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or		
		US-20020013910-\$ of US-20010044070-\$ of US-20030039910-\$ of US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near		
		stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj		
	,	delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near5 (agent))		
		(((ped (post-exposure adj delay) (post adj exposure adj delay)) near6		
		stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) ((((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near6		
		stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10		1
		\$10thiolsulfonate\$10)))) AND (((acid photoacid) near generat\$4)		
		(photoactive near compound))		
-	111	(((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE)	USPAT;	2003/09/03 14:42
		SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT	US-PGPUB;	
		((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$	EPO; JPO;	
		or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or	DERWENT	
		US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or		
		US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or		
		US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near		
		stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj		
		delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near5 (agent))		
		(((ped (post-exposure adj delay) (post adj exposure adj delay)) near6		
		stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) ((((ped		
		(post-exposure adj delay) (post adj exposure adj delay)) near6		
		stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10		
	L	\$10thioIsulfonate\$10)))) AND surfactant		

-	0	(((((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay))) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay)) post adj exposure adj delay)) near5 (agent))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:04
		(((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) ((((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)))) AND surfactant) AND (430/\$.CCLS.)		
-	5	(("5589312") or ("5344694")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:05
-	2	wo-9306529-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:06
-	7	((("5589312") or ("5344694")).PN.) or wo-9306529-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:06
-	8055	(430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 18:43
-	31	((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.) and ((thiol disulfide thiolsulfonate) near derivative)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:22
-	31	(((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.) and ((thiol disulfide thiolsulfonate) near derivative)) not (((("5589312") or ("5344694")).PN.) or wo-9306529-\$.did.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:22
	31	((((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.) and ((thiol disulfide thiolsulfonate) near derivative)) not (((("5589312") or ("5344694")).PN.) or wo-9306529-\$.did.)) not (((((THIOL DISULFIDE THIOLSULFONATE)) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay)) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay)) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay)) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 15:22
		\$10thiolsulfonate\$10))))		

	30	(((((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.) and ((thiol disulfide thiolsulfonate) near derivative)) not (((("5589312") or ("5344694")).PN.) or wo-9306529-\$.did.)) not (((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or US-20030148211-\$ or US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))))) NOT (((ped (post-exposure adj delay)) (post adj exposure adj delay) (post adj exposure adj delay) (post adj exposure adj delay) (post adj exposure adj delay) (post adj exposure adj delay) (post adj exposure adj delay) (post adj exposure adj delay) (post adj exposure adj delay) (post adj exposure adj delay) (post adj exposure adj delay) (post adj exposure adj delay) (post adj exposure adj delay) (post adj exposure adj delay) (post adj exposure adj delay) (post adj exposure adj delay) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay)) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) (((ped (post-exposure adj delay)) (post adj exposure adj delay)) near6 stabil\$6) and (resist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 16:59
		photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10		
		()))		
-	246076	stabilizer	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 17:51
-	12420	stabilizer and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 16:59
-	17642	((acid photoacid) near generat\$4) (photoactive near compound)	USPAT; US-PGPUB; EPO; JPO;	2003/09/03 16:59
-	22496	(basic adj compound) (nitrogen-containing adj compound)	DERWENT USPAT; US-PGPUB; EPO; JPO;	2003/09/03 16:59
-	266458	surfactant	DERWENT USPAT; US-PGPUB; EPO; JPO;	2003/09/03 16:59
-	1096	dissolution adj inhibitor	DERWENT USPAT; US-PGPUB; EPO; JPO;	2003/09/03 17:00
-	42	(stabilizer and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant and (dissolution adj inhibitor)	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 17:00

-	41	((stabilizer and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant and (dissolution adj inhibitor)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay)) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay)) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) ((((ped (post-exposure adj delay)) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) (((stabilizer and (resist photoresist)) and (((acid photoacid) near generat\$4) (photoactive near compound)) and ((basic adj compound) (nitrogen-containing adj compound)) and surfactant and (dissolution adj inhibitor)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate)	USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 17:01 2003/09/03 17:02
		(post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay)) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) ((((ped (post-exposure adj delay)) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)))) not (((((430/270.1 430/926 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.) and ((thiol disulfide thiolsulfonate) near derivative)) not (((("5589312")) or ("5344694")).PN.) or wo-9306529-\$.did.)) not ((((THIOL DISULFIDE THIOLSULFONATE) NEAR5 DERIVATIVE) SAME STABIL\$6) AND (RESIST PHOTORESIST)) NOT ((US-6489080-\$ or US-6395446-\$ or US-6180316-\$ or US-6280897-\$ or US-6090518-\$ or US-6399272-\$).did. or (US-20020136981-\$ or US-20030148211-\$ or		
		US-20030039916-\$ or US-20020058206-\$ or US-20020015916-\$ or US-20010044070-\$ or US-20030039918-\$ or US-20020147259-\$).did. or (JP-2002303986-\$).did.)) NOT (((ped (post-exposure adj delay) (post adj exposure adj delay)) near stabilizer) ((ped (post-exposure adj delay) (post adj exposure adj delay)) same ((thiol disulfide thiolsulfonate) near derivative)) ((ped (post-exposure adj delay)) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay)) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) ((((ped (post-exposure adj delay)) post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))))) NOT (((ped (post-exposure adj delay)) (post adj exposure adj delay)) near stabilizer) (((ped (post-exposure adj delay)) delay)) (post adj exposure adj delay)) same (((thiol disulfide))		,
		thiolsulfonate) near derivative)) ((ped (post-exposure adj delay) (post adj exposure adj delay)) near5 (agent)) (((ped (post-exposure adj delay)) (post adj exposure adj delay)) near6 stabil\$6) same ((thiol disulfide thiolsulfonate) near derivative)) ((((ped (post-exposure adj delay)) (post adj exposure adj delay)) near6 stabil\$6) and (resist photoresist)) and (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))))		
-	855	stabilizer and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 18:01
-	1	(stabilizer same ((thiol disulfide thiolsulfonate) near derivative)) and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/03 17:53

		•		
-	53	stabilizer same ((thiol disulfide thiolsulfonate) near derivative)	USPAT; US-PGPUB;	2003/09/03 17:54
			EPO; JPO;	
	854	(stabilizer and (//20/270.1.420/200.420/220.420/220.420/227	DERWENT	2002/00/02 10 02
-	034	(stabilizer and ((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)) not (stabilizer same ((thiol	USPAT; US-PGPUB;	2003/09/03 18:02
		disulfide thiolsulfonate) near derivative))	EPO; JPO;	
			DERWENT	
-	706	(stabilizer and ((430/270.1 430/296 430/326 430/330 430/327	USPAT	2003/09/03 18:02
		430/913 430/917 430/921 430/942).ccls.)) not (stabilizer same ((thiol disulfide thiolsulfonate) near derivative))		
_	116	stabil\$6 same ((thiol disulfide thiolsulfonate) near derivative)	USPAT;	2003/09/03 18:50
			US-PGPUB;	
			EPO; JPO;	
	4	(stabil\$6 same ((thiol disulfide thiolsulfonate) near derivative)) and	DERWENT USPAT;	2003/09/03 18:51
		(resist photoresist)	US-PGPUB;	2003/09/03 16:31
			EPO; JPO;	
			DERWENT	
-	8055	(430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.	USPAT;	2003/09/03 18:43
		430/321 430/342/.CCIS.	US-PGPUB; EPO; JPO;	
			DERWENT	
-	2163	(thiol disulfide thiolsulfonate) near derivative	USPAT;	2003/09/03 18:50
		·	US-PGPUB;	
			EPO; JPO; DERWENT	
-	126948	\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10	USPAT;	2003/09/03 18:44
			US-PGPUB;	
			EPO; JPO;	
-	127073	((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10	DERWENT USPAT;	2003/09/03 18:50
		\$10disulfide\$10 \$10thiolsulfonate\$10)	US-PGPUB;	2003/03/03 10:30
			EPO; JPO;	
_	10164	stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative)	DERWENT USPAT;	2003/09/03 18:50
		(\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))	US-PGPUB;	2003/03/03 10.30
			EPO; JPO;	
	701	(stabile come (()) bind disulted abid all of come of the come of the come	DERWENT	0000/00/00 10
-	701	(stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist	USPAT; US-PGPUB;	2003/09/03 19:55
		photoresist)	EPO; JPO;	
			DERWENT	
-	34	((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative)	USPAT;	2004/07/07 12:51
		(\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1 430/296 430/326 430/330 430/327	US-PGPUB; EPO; JPO;	
		430/913 430/917 430/921 430/942).ccls.)	DERWENT	
-	6896	(((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10	USPAT;	2003/09/03 19:55
		\$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)	US-PGPUB;	
			EPO; JPO; DERWENT	
-	527	((((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10	USPAT;	2003/09/03 19:55
		\$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)) and	US-PGPUB;	
		((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.)	EPO; JPO; DERWENT	
-	493	((((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10	USPAT;	2003/09/03 19:55
		\$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)) and	US-PGPUB;	
		((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917	EPO; JPO;	
		430/921 430/942).ccls.)) not (((stabil\$6 same (((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10	DERWENT	
		\$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1		
		430/296 430/326 430/330 430/327 430/913 430/917 430/921		
L		430/942).ccls.))		

-	233	((((((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)) and	USPAT; US-PGPUB;	2003/09/03 19:59
		((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917	EPO; JPO;	
		430/921 430/942).ccls.)) not (((stabil\$6 same (((thiol disulfide	DERWENT	
		thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10	DERWEINT	
		\$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1		
		430/296 430/326 430/330 430/327 430/913 430/917 430/921		
		430/942).ccls.))) and (\$5acid near generat\$3)		
_	233	(((((((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10	USPAT;	2003/09/03 19:59
		\$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)) and	US-PGPUB;	2003/03/03 13.39
		((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917	EPO; JPO;	
		430/921 430/942).ccls.)) not (((stabil\$6 same (((thiol disulfide	DERWENT	
		thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10		
İ		\$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1		
		430/296 430/326 430/330 430/327 430/913 430/917 430/921		
	,	430/942).ccls.))) and (\$5acid near generat\$3)) not (((stabil\$6 same		
		(((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10		
		\$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist photoresist))		
		and ((430/270.1 430/296 430/326 430/330 430/327 430/913		
		430/917 430/921 430/942).ccls.))		
-	233	(((((((thiol disulfide thiolsulfonate) near derivative) (\$10thiol\$10	USPAT;	2003/09/03 19:59
		\$10disulfide\$10 \$10thiolsulfonate\$10)) and (resist photoresist)) and	US-PGPUB;	
		((430/270.1 430/296 430/326 430/330 430/327 430/913 430/917	EPO; JPO;	
		430/921 430/942).ccls.)) not (((stabil\$6 same (((thiol disulfide	DERWENT	
		thiolsulfonate) near derivative) (\$10thiol\$10 \$10disulfide\$10		
		\$10thiolsulfonate\$10))) and (resist photoresist)) and ((430/270.1		
		430/296 430/326 430/330 430/327 430/913 430/917 430/921 430/942).ccls.))) and (\$5acid near generat\$3)) not (((stabil\$6 same		
		(((thiol disulfide thiolsulfonate) near derivative (\$10thiol\$10		
		\$10disulfide\$10 \$10thiolsulfonate\$10))) and (resist photoresist))		
		and ((430/270.1 430/296 430/326 430/330 430/327 430/913		•
		430/917 430/921 430/942).ccls.))) and ((430/270.1 430/296 430/326		
		430/330 430/327 430/913 430/917 430/921 430/942).ccls.)		
-	2	(("6406828") or ("6218076")).PN.	USPAT;	2004/06/29 13:23
			US-PGPUB;	
			EPO; JPO	
-	2	(("20010044070") or ("6395446")).PN.	USPAT;	2004/06/29 13:39
			US-PGPUB;	
			EPO; JPO	
-	37	((((\$10thiol\$10 \$10disulfide\$10 \$10thiolsulfonate\$10) and (resist	USPAT;	2004/06/29 14:01
		photoresist)) and (((acid photoacid) near generat\$4) (photoactive near	US-PGPUB;	
		compound)) and ((basic adj compound) (nitrogen-containing adj	EPO; JPO;	
		compound)) and surfactant) and (dissolution adj inhibitor)) not ((((thiol disulfide thiolsulfonate mercapto\$) and (ped (post-exposure	DERWENT	
		adj delay) (post adj exposure adj delay)) and (resist photoresist) and		
1		(((acid photoacid) near generat\$4) (photoactive near compound))) and		
		(surfactant (dissolution adj inhibitor) ((basic adj compound)		
		(nitrogen-containing adj compound)))) not ((thiol disulfide		
		thiolsulfonate mercapto\$) same (ped (post-exposure adj delay) (post		
		adj exposure adj delay))))		
-	3	(("6280897") or ("4304841") or ("6406828")).PN.	USPAT;	2004/07/07 11:08
		, , , , , , , , , , , , , , , , , , , ,	US-PGPUB;	
			EPO; JPO	
-	1 <i>7</i> 800	(thiol disulfide thiolsulfonate mercapto\$) adj (compound derivative)	USPAT;	2004/07/06 19:04
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	450751	photoresist resist	USPAT;	2004/07/06 19:04
			US-PGPUB;	
			EPO; JPO;	
L			DERWENT	

-	5152	(photoacid acid) adj generator	USPAT;	2004/07/06 19:04	٦
]	Aprilia dela, adj generator	US-PGPUB;	2004/0//00 19:04	
			EPO; JPO;		l
			DERWENT		
-	1098651	solvent	USPAT;	2004/07/06 19:04	1
	1030031	Sorveine	US-PGPUB;	2004/07/06 19:04	1
					ĺ
			EPO; JPO; DERWENT		
-	35	((thiol disulfide thiolsulfonate mercapto\$) adj (compound derivative))		2004/07/06 10:00	
		and (photoresist resist) and ((photoacid acid) adj generator) and	USPAT;	2004/07/06 19:08	l
		solvent	US-PGPUB;		l
		Solvent	EPO; JPO;		
_	0	jp-5550806-\$.did.	DERWENT	2004/07/06 40 00	
)p-5550000-#.did.	USPAT;	2004/07/06 19:09	
			US-PGPUB;		l
			EPO; JPO;		i
-	0	jp-55050806-\$.did.	DERWENT	2024/2=/2542.00	
_)p-55050000-\$.did.	USPAT;	2004/07/06 19:09	
			US-PGPUB;		
			EPO; JPO;		1
	0	in EE00E0006 ¢ did	DERWENT		l
-	"	jp-550050806-\$.did.	USPAT;	2004/07/06 19:09	
			US-PGPUB;		
			EPO; JPO;		
		:- FC7FC40 A 1: 1	DERWENT		l
-	0	jp-5675643-\$.did.	USPAT;	2004/07/06 19:09	١
			US-PGPUB;		
	ļ		EPO; JPO;		
		: FC07FC42 # 1:1	DERWENT		
-	1	jp-56075643-\$.did.	USPAT;	2004/07/06 19:09	
			US-PGPUB;		
			EPO; JPO;		
	l l	i	DERWENT		1